United States Patent and Trademark Office

UNITED STATES DEPARTMENT OF COMMERCE United States Patent and Trademark Office Address: COMMISSIONER FOR PATENTS P.O. Box 1450 Alexandria, Virginia 22313-1450 www.uspto.gov

APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
10/718,789	11/24/2003	Kazunori Hagimoto	SUG-176-USAP	1591
28892 SNIDER & AS	7590 01/08/2007 SSOCIATES	EXAMINER		
P. O. BOX 27613			WEISS, HOWARD	
WASHINGTON, DC 20038-7613			ART UNIT	PAPER NUMBER
		•	2814	
SHORTENED STATUTOR	RY PERIOD OF RESPONSE	MAIL DATE	DELIVERY MODE	
3 MONTHS		01/08/2007	PAPER	

Please find below and/or attached an Office communication concerning this application or proceeding.

If NO period for reply is specified above, the maximum statutory period will apply and will expire 6 MONTHS from the mailing date of this communication.

	Application No.	Applicant(s)	
Office Action Commence	10/718,789	HAGIMOTO ET AL.	
Office Action Summary	Examiner	Art Unit	
	Howard Weiss	2814	
The MAILING DATE of this communication app Period for Reply	ears on the cover sheet with the c	orrespondence address	
A SHORTENED STATUTORY PERIOD FOR REPLY WHICHEVER IS LONGER, FROM THE MAILING DA - Extensions of time may be available under the provisions of 37 CFR 1.13 after SIX (6) MONTHS from the mailing date of this communication. - If NO period for reply is specified above, the maximum statutory period w - Failure to reply within the set or extended period for reply will, by statute, Any reply received by the Office later than three months after the mailing earned patent term adjustment. See 37 CFR 1.704(b).	ATE OF THIS COMMUNICATION 16(a). In no event, however, may a reply be time The company and will expire SIX (6) MONTHS from the cause the application to become ABANDONE	I. lely filed the mailing date of this communication. O (35 U.S.C. § 133).	
Status			
 Responsive to communication(s) filed on 15 No. This action is FINAL. 2b) This Since this application is in condition for allowar closed in accordance with the practice under E. 	action is non-final. nce except for formal matters, pro		
Disposition of Claims			
4) Claim(s) 33-38 ts/are pending in the application 4a) Of the above claim(s) is/are withdrav 5) Claim(s) is/are allowed. 6) Claim(s) 33-38 is/are rejected. 7) Claim(s) is/are objected to. 8) Claim(s) are subject to restriction and/or Application Papers 9) The specification is objected to by the Examine 10) The drawing(s) filed on is/are: a) access	vn from consideration. r election requirement.	Examiner.	
Applicant may not request that any objection to the carection Replacement drawing sheet(s) including the correction The oath or declaration is objected to by the Ex	drawing(s) be held in abeyance. Section is required if the drawing(s) is obj	e 37 CFR 1.85(a). ected to. See 37 CFR 1.121(d).	
Priority under 35 U.S.C. § 119	•		
 12) Acknowledgment is made of a claim for foreign a) All b) Some * c) None of: 1. Certified copies of the priority documents 2. Certified copies of the priority documents 3. Copies of the certified copies of the prior application from the International Bureau * See the attached detailed Office action for a list of the certified copies of the certified copies of the prior application from the International Bureau 	s have been received. s have been received in Applicati ity documents have been receive (PCT Rule 17.2(a)).	on No ed in this National Stage	
Attachment(s) 1) Notice of References Cited (PTO-892) 2) Notice of Draftsperson's Patent Drawing Review (PTO-948) 3) Information Disclosure Statement(s) (PTO/SB/08) Paper No(s)/Mail Date	4) Interview Summary Paper No(s)/Mail Da 5) Notice of Informal P 6) Other:	ate	

Application/Control Number: 10/718,789

Art Unit: 2814

Attorney's Docket Number: SUG-176-USAP

Filing Date: 11/24/03

Continuing Data: RCE established 11/15/2006

Claimed Foreign Priority Date: 11/28/2002, 12/25/2002, 1/31/2003, 8/29/2003

Applicant(s): Hagimoto et al. (Noto)

Examiner: Howard Weiss

Continued Examination Under 37 CFR 1.114

1. A request for continued examination under 37 CFR 1.114, including the fee set forth in 37 CFR 1.17(e), was filed in this application after final rejection. Since this application is eligible for continued examination under 37 CFR 1.114, and the fee set forth in 37 CFR 1.17(e) has been timely paid, the finality of the previous Office action has been withdrawn pursuant to 37 CFR 1.114. Applicant's submission filed on 11/15/2006 has been entered.

Claim Objections

2. Claim 38 recites the limitation "the Ag-base layer" in Line 19. There is insufficient antecedent basis for this limitation in the claim.

Claim Rejections - 35 USC § 103

- 3. The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:
 - (a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.
- Claims 33 to 38 are rejected under 35 U.S.C. 103(a) as being unpatentable over Yasutimi et al. (JP 2001-339100), Carter-Coman et al. (U.S. Patent No. 6,222,207), Burt (U.S. Patent No. 4,574,470), Gee et al. (U.S. Patent No. 6,969,874) and Murasato et al. (U.S. Patent No. 5,744,829).

Page 2

Art Unit: 2814

Yasutimi et al. show most aspects of the instant invention (e.g. Figure 2) including:

- ➤ A compound semiconductor layer 4 including a light-emitting layer consisting of N-type AlGaInP cladding layer 41, an AlGaInP active layer 42 and a P-type AlGaInP cladding layer 43 and a light extraction surface 44 and sensitive to the wavelength ranges listed
- > A silicon device substrate 2 bonded to said compound semiconductor layer
- > A multilayered metal reflective layer 3

Yasutimi et al. do not show the metal reflective layer being Pd/Ag alloy or Ag, Ru, Rh, Re, Os, Ir and Pt based, an Ag-based contact layer as claimed and a silicon-diffusion-blocking layer of the composition claimed and the layers in the light-emitting layer to be explicitly composed of $(Al_xGa_{1-x})_yln_{1-y}P$ where $0 \le x \le 1$ and $1 \le y \le 1$ (Here $1 \le y \le 1$ is taken to mean y=1).

Carter-Coman et al. teach (e.g. Figures 2) to make a metal reflective layer **34** Agbased, a contact layer **32** and a silicon-diffusion-blocking layer **36** made of a conductive material with Ti or Ni as a major component (e.g. NiV) to produce an light emitting device with high reflectivity after subjected to high temperatures (Column 2 Lines 23 to 34). It would have been obvious to a person of ordinary skill in the art at the time of invention to make a metal reflective layer Ag-based, a contact layer and a silicon-diffusion-blocking layer as taught by Carter-Coman et al. in the device of Yasutimi et al. to produce an light emitting device with high reflectivity after subjected to high temperatures.

Burt teaches (e.g. Column 6 Lines 41 to 47) that NiV inherently blocks silicon diffusion. The express, implicit, and inherent disclosures of a prior art reference may be relied upon in the rejection of claims under 35 U.S.C. 102 or 103. "The inherent teaching of prior art reference, a question of fact, arises both in the context of anticipation and obviousness." *In re Napier, 55 F.3d 610, 613, 34 USPQ2d 1782, 1784 (Fed. Cir.1995)* (affirmed a 35 U.S.C. 103 rejection based in part on inherent

Application/Control Number: 10/718,789

Art Unit: 2814

disclosure in one of the references). See also In re Grasselli, 713 F.2d 731, 739, 218 USPQ 769, 775 (Fed.Cir. 1983).

Gee et al. teach (e.g. Figures 3 and 4) to make ohmic contacts 20, reflective layers 24 and diffusion barriers of Pd/Ag alloy or Ag, Ru, Rh, Re, Os, Ir and Pt based (Column 4 Lines 36 to Column 38) to provide a low resistance, good optical reflectance, good adhesion and to control unwanted diffusion during annealing (Column 4 Line55 to Column 5 Line 1). It would have been obvious to a person of ordinary skill in the art at the time of invention to make ohmic contacts, reflective layers and diffusion barriers of Pd/Ag alloy or Ag, Ru, Rh, Re, Os, Ir and Pt based as taught by Gee et al. in the device of Yasutimi et al. to provide a low resistance, good optical reflectance, good adhesion and to control unwanted diffusion during annealing.

Murasato et al. teach (e.g. Figure 1 and Column 3 Lines 55 to 63 and Column) to use double hetero-structure $(Al_xGa_{1-x})_vIn_{1-v}P$ where $0 \le x \le 1$ and $1 \le y \le 1$ in cladding layers 5,7 and active layer 6 to provide a high brightness, low operating voltage and high reliability device (Column 2 Lines 65 to 67). It would have been obvious to a person of ordinary skill in the art at the time of invention to use double heterostructure (Al_xGa_{1-x})_vIn_{1-v}P where 0≤x≤1 and 1≤y≤1 in cladding layers and active layer as taught by Murasato et al. in the device of Yasutimi et al. to provide a high brightness, low operating voltage and high reliability device.

Response to Arguments

5. Applicant's arguments with respect to Claims 33 to 38 have been considered but are moot in view of the new ground(s) of rejection.

Conclusion

6. Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published

applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at **866-217-9197** (toll-free).

- 7. Papers related to this application may be submitted directly to Art Unit 2814 by facsimile transmission. The faxing of such papers must conform with the notice published in the Official Gazette, 1096 OG 30 (15 November 1989). The Art Unit 2814 Fax Center number is (571) 273-8300. The Art Unit 2814 Fax Center is to be used only for papers related to Art Unit 2814 applications.
- 8. Any inquiry concerning this communication or earlier communications from the examiner should be directed to Howard Weiss at (571) 272-1720 and between the hours of 7:00 AM to 3:00 PM (Eastern Standard Time) Monday through Friday or by e-mail via Howard.Weiss@uspto.gov. If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Wael Fahmy, can be reached on (571) 272-1705.
- 9. The following list is the Examiner's field of search for the present Office Action:

Field of Search	Date
U.S. Class / Subclass(es): 257/ 96, 98	thru 1/3/2007
Other Documentation: none	
Electronic Database(s): EAST	thru 1/3/2007

HW/hw 3 January 2007 Howard Weiss Primary Examiner Art Unit 28/14